

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of :  
Tomohiro OKUMURA et al. : Attn: APPLICATION BRANCH  
Serial No. NEW : Docket No. 2001\_1089A  
Filed August 1, 2001 :

PLASMA PROCESSING METHOD AND  
APPARATUS THEREOF

THE COMMISSIONER IS AUTHORIZED  
TO CHARGE ANY DEFICIENCY IN THE  
FEE FOR THIS PAPER TO DEPOSIT  
ACCOUNT NO. 23-0975.

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents,  
Washington, DC 20231

Sir:

Prior to initial examination of the above-identified new patent application,  
kindly amend the application as follows:

IN THE CLAIMS:

Kindly amend claims 29 and 37 as follows:

29.(Amended)

A plasma processing apparatus as defined in claim 27, wherein  
the dielectric tube is disposed such that (it) covers an edge of a hole of the metal body or  
(the facing electrode).

37.(Amended)

A plasma processing apparatus as defined in claim 28, wherein  
the dielectric tube is disposed such that (it) covers an edge of a hole of the metal body or  
(the facing electrode).